# (19) World Intellectual Property Organization International Bureau



### ! (CLUD 131110) | 1 (CLUX 1011 1011 1011 1013 1013 1014 10 10 XIXIX (CLUX 1010 1011 1011 1011 1011 1011 1011 1

(43) International Publication Date 26 February 2004 (26.02.2004)

PCT

## (10) International Publication Number WO 2004/017335 A1

- (51) International Patent Classification7: H01B 3/02, 3/30, 3/46, B32B 3/26, C08G 65/00, 77/04
- (21) International Application Number:

PCT/US2002/026276

- (22) International Filing Date: 15 August 2002 (15.08.2002)
- (25) Filing Language:

Englis

(26) Publication Language:

English

- (71) Applicant (for all designated States except US): HON-EYWELL INTERNATIONAL INC. [US/US]; PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US).
- (72) Inventors; and
- (75) Inventors/Applicants (for US only): HACKER, Nigel [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). LEFFERT, Scott [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). FIGGE, Lisa [US/US];

HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). SPEAR, Richard [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07962 (US). BEDWELL, William [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). RAMOS, Teresa [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US).

- (74) Agents: FISH, Robert et al.; RUTAN & TUCKER, LLP, 611 Anton Blvd., 14th Floor, Costa Mesa, CA 92626 (US).
- (81) Designated States (national): AE, AG, AL, AM, AT (utility model), AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ (utility model), CZ, DE (utility model), DE, DK (utility model), DK, DM, DZ, EC, EE (utility model), EB, ES, FI (utility model), FI, GB, GD, GB, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK (utility model), SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

[Continued on next page]

(54) Title: NANOPOROUS MATERIALS AND METHODS OF FORMATION THEREOF

(57) Abstract: Low dielectric materials are described herein that comprise a plurality of pores or nanopores in addition to the ultrananopores. It is further contemplated that the low dielectric materials described herein will have a dielectric constant of less than about 3. The dielectric materials are fromed from polymer compositions, wherein the polymer compositions comprise a plurality of monomersand wherein at least one monomer comprises a radical precursor bonded to a structural precursor. Further, methods of forming dielectric materials from polymer compositions are presented. The figure shows the chemical structure for a methyl/t-butyl Low organic Content/Low Organic Siloxane Polymer.

VO 2004/017335 A1

#### WO 2004/017335 A1



(84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

#### Published:

with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

#### INTERNATIONAL SEARCH REPORT

International application No.

PCT/US02/26276

		FC170302120270	
IPC(7) US CL	SIFICATION OF SUBJECT MATTER : H01B 3/02, 3/30, 3/46; B32B 3/26; C08G 65/00 : 252/570,573; 428/304.4,312.6,447; 521/154,180	); 525/390,416,474,534	·:
	International Patent Classification (IPC) or to both nati	onal classification and IPC	
Minimum doc	OS SEARCHED  umentation searched (classification system followed by 2/570,573; 428/304.4,312.6,447; 521/154,180; 525/3		
Documentatio	n searched other than minimum documentation to the e	extent that such documents are included in	the fields searched
	a base consulted during the international search (name intinuation Sheet	of data base and, where practicable, sear	ch terms used)
C. DOCU	MENTS CONSIDERED TO BE RELEVANT		
Category *	Citation of document, with indication, where ap	propriate, of the relevant passages	Relevant to claim No.
X,P	US 6,472,076 B1 (HACKER) 29 October 2002 (29.1 column 11, lines 1-67, column 12, lines 37-67, column		1, 3-6, 7, 9, 11, 15-19, 28, 32, 33, 35-38, 40
х	US 6,107,357 A (HAWKER et al) 22 August 2000 (2 column 5, line 33, column 5, line 53 through column column 10, lines 6-63, column 11, lines 27-60.		1-9, 11-21, 23, 24, 26- . 40
x	US 6,143,360 A (ZHONG) 07 November 2000 (07.11.2000), column 3, lines 30-66, column 6, lines 39-67.		1-7, 9, 11-21, 23, 24, 26-38, 40
х	US 6,156,812 A (LAU et al) 05 December 2000 (05. column 7, line 53 through column 8, line 56, column 51.		1-3, 14, 16-21, 23, 24,26-32, 38
A	US 6,177,143 B1 (TREADWELL et al) 23 January 2 62.	2001 (23.01.2001), column 2, lines 19-	1-41
A	US 6,235,353 B1 (DRAGE et al) 22 May 2001 (22.0	5.2001), column 2, lines 38-55.	1-41
	documents are listed in the continuation of Box C.	See patent family annex.	
Special categories of cited documents:  "A"  document defining the general state of the art which is not considered to be of particular relevance		"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention	
	plication or patent published on or after the international filing date	"X" document of particular relevance; the considered novel or cannot be conside when the document is taken alone	
	t which may throw doubts on priority claim(s) or which is cited to the publication date of another citation or other special reason (as	"Y" document of particular relevance; the considered to involve an inventive ste combined with one or more other suc	p when the document is
	t referring to an oral disclosure, use, exhibition or other means	being obvious to a person skilled in the	
	t published prior to the international filing date but later than the late claimed	"&" document member of the same patent family	
Date of the actual completion of the international search		Date of mailing of the international search report	
20 November 2002 (20.11.2002)  Name and mailing address of the ISA/US		Archarized officer	
Commissioner of Patents and Trademarks Box PCT		Jeffrey B. Robertson	
Washington, D.C. 20231 Facsimile No. (703)305-3230		Telephone No. (703) 308-0661	

Form PCT/ISA/210 (second sheet) (July 1998)

INTERNATIONAL SEARCH REPORT	PCT/US02/26276
	,
	·-
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organopolysiloxane, organohydridosiloxane, org	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane, silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3: EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organohydridosiloxane, and organohydridosiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organopolysiloxane, org	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane, silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3: EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosilo	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane, silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3: EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosilo	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane,silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3: EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organohydridosiloxane, adamantane, pore, nanometer, polysiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organohydridosiloxane, organopolysiloxane, organohydridosiloxane, organopolysiloxane, organopolysiloxane, organopolysiloxane, organohydridosiloxane, organopolysiloxane, organopolysiloxa	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane, silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane,	rial, dielectric costant, radical precursor, structural polyorganosiloxane, polydiorganosiloxane, xane, silsesquioxane, polysilsesquioxane.
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosilo	\ <u>.</u>
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organohydridosiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane, organohydr	\ <u>.</u>
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosilo	\ <u>.</u>
Continuation of B. FIELDS SEARCHED Item 3:  EAST search, search terms: ultrananopore, ultrananoporous, dielectric mate precursor, adamantane, pore, nanometer, polysiloxane, organopolysiloxane, diorganopolysiloxane, silicone, siloxane, hydridosiloxane, organohydridosiloxane,	\ <u>.</u>

Form PCT/ISA/210 (second sheet) (July 1998)